

ABSTRACT

5 A transparent amorphous silicon dioxide film containing many fine voids, characterized in that the refractive index (for light at $\lambda = 500$ nm) is in the range of 1.01 to 1.40 and that 80 vol.% or more of the fine
10 voids have a diameter of 5 nm or less, has a low refractive index and excellent physical strength such as high scratch resistance, so that it is advantageously employable as an optical film of an optical device for various uses.